PUREON

Highlights

– Highly economical

– Superior wetting ability

– Free rinsing – leaves no film or residue

– Fully compatible with other VECTOR products

Detergent

VECTOR HTC-SCA-1

VECTOR HTC-SCA series are water-based detergents formulated to increase the cavitational energy released upon the substrate surface by ultrasonic or megasonic apparatus. The products are designed for more effective cleaning of post-lapped, post-etched and post-polished substrates. Used at economical dilution ratios, VECTOR HTC-SCA series will remove light organics, polymers and sub-micron particles typically found on the surface of semiconductor materials. These contaminants are often the cause of wafer staining and streaking upon examination after etch.

VECTOR HTC-SCA series detergents are recommended for pre-cleaning and final cleaning stages of solar silicon production lines, wherever ultrasonic cleaning is applied. These products will remove organic and inorganic contamination and particles from both mono-crystalline and multi-crystalline silicon. VECTOR HTC-SCA series can be used in heated or unheated ultrasonic tanks, and are also recommended for brush and dip tank applications.

Typical applications
Gallium nitride, gallium arsenide, germanium, sapphire, silicon, silicon carbide

Slurry additive	Base material	Dilution ratio	pH value	Specific gravity
VECTOR HTC-SCA-1	Water	25:1	9.2	1.05
VECTOR HTR	Water	30:1	9.8	1.03

VECTOR HTC-SCA-1 has been optimized for cleaning of gallium nitride, gallium arsenide, germanium, sapphire, and silicon and silicon carbide substrates.

Pureon offers a wide range of customized solutions. Get in touch with us.

Product specifications

Base material	Water
Shelf life	24 months

Order information

Packing	Product is available in 5-gallon pails and 55-gallon drums. Other sizes available upon request.
Unit of measure	Gallon [gal]

Application recommendations

Handling	It is recommended that evaluation of VECTOR HTC-SCA Series begin at dilutions of 4 % mixed with deionized (DI) water, although tap water that does not contain hard water ions is also acceptable. Since the type and degree of residue to be removed varies, these factors will ultimately determine specific “in-house” dilutions. Other factors to consider include wafer exposure time and the power of the ultrasonic equipment in use.
Storage	Product should be stored in a temperature controlled environment. Prolonged exposure to temperatures at or below 32 ° Fahrenheit (0 °C) is discouraged. Prolonged exposure to temperatures at or above 100 ° Fahrenheit (38 °C) is also discouraged. In addition, material should always be sealed when not in use to prevent evaporation.
Disposal	Dispose of in accordance with all applicable local regulations.

This product is manufactured by Intersurface Dynamics.

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